



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application  
SC/Serial No.: **SEE SCHEDULE A**  
Filed: **SEE SCHEDULE A**  
Title: **SEE SCHEDULE A**

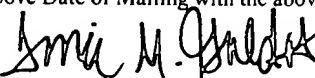
PATENT APPLICATION

Customer No. 23910

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Signature Date: January 15, 2003 (Signature)

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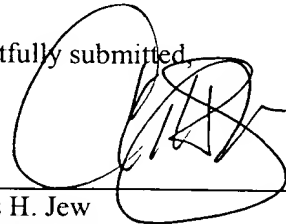
I am the attorney of record for the patents and patent applications listed on Schedule A attached hereto. Please be notified that my address has changed to the following:

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Please send all future correspondence concerning the patent and patent applications listed on Schedule A to the above address.

Respectfully submitted,

Date: 1-15-03

By:   
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SCHEDULE A  
LIST OF ISSUED PATENTS

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Title	Filing Date	U.S. Serial No.	Issue Date	Patent No.	Old (BDO) Attorney Docket No.	NEW Docket No.
1. Free-Piston Engine	6/25/1998	09/104,895	3/31/2001	6,199,519	023890-002	SAND-01002US0
2. Diffractive Element In Extreme-UV Lithography Condenser	8/6/1998	09/130,224	9/12/2000	6,118,224	023890-003	SAND-01003US0
3. Monolithic Pattern-Sensitive Detector	06/12/1998	09/096,598	10/10/2000	6,130,431	023890-004	SAND-01004US0
4. Extreme-UV Lithography Condenser	2/11/1999	09/249,738	4/3/2001	6,210,865	023890-005	SAND-01005US0
5. Wafer Chamber Having A Gas Curtain for Extreme-UV Lithography	11/6/1998	09/187,911	3/6/2001	6,198,792	023890-006	SAND-01006US0
6. Low Thermal Distortion Extreme-UV Lithography Reticle	8/24/1998	09/139,149	11/13/2001	6,316,150	023890-007	SAND-01007US0
7. Extreme-UV Lithography System	5/4/1999	09/305,172	5/1/2001	6,225,027	023890-008	SAND-01008US0
8. Extreme-UV Lithography Vacuum Chamber Zone Seal	1/13/1999	09/229,826	12/25/2001	6,333,775	023890-009	SAND-01009US0
9. Light Weight High-Stiffness Stage Platen	6/16/1999	09/334,702	2/13/2001	6,188,150	023890-011	SAND-01011US0

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	Title	Filing Date	U.S. Serial No.	Issue Date	Patent No.	Old (BL) Attorney Docket	New Attorney Docket No.
10.	Thermophoretic Vacuum Wand	12/11/1998	09/210,348	6/6/2000	6,072,157	023890-012	SAND-01012US0
11.	Method and Apparatus for Reducing Sample Dispersion in Turns and Junctions of Microchannel System	4/26/1999	09/299,269	8/7/2001	6,270,641	023890-013	SAND-01013US0
12.	Electrostatically Screened, Voltage-Controlled Electrostatic Chuck	3/12/1999	09/268,166	1/2/2001	6,169,652	023890-014	SAND-01014US0
13.	Extreme-UV Scanning Wafer and Reticle Stages	10/29/1999	09/430,858	3/5/2002	6,353,271	023890-015	SAND-01018US0
14.	Projection Lithography with Distortion Compensation Using Reticle Chuck Contouring	07/20/1999	09/357,613	5/8/2001	6,229,871	023890-016	SAND-01019US0
15.	Condenser For Extreme-UV Lithography With Discharge Source	1/21/2000	09/489,163	9/4/2001	6,285,737	023890-017	SAND-01022US0
16.	Extreme-UV Electrical Discharge Source	6/13/2000	09/594,746	3/12/2002	6,356,618	023890-018	SAND-01028US0
17.	Diffraction Spectral Filter for Use in Extreme-UV Lithography Condenser	8/4/2000	09/631,617	10/22/2002	6,469,827	023890-019	SAND-01033US0
18.	Thermophoretic Vacuum Wand	3/23/2000	09/533,600	5/15/2001	6,232,578	023890-020	SAND-01034US0
19.	Motorized Support Jack	5/10/2000	09/568,611	12/11/2001	6,328,282	023890-021	SAND-01035US0

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	Title	Filing Date	U.S. Serial No.	Issue Date	Patent No.	Old (BDSM) Attorney Docket No.	New Attorney Docket No.
20.	Illumination System Having a Plurality of Movable Sources	10/2/2000	09/678,419	5/28/2002	6,396,068	023890-037	SAND-01037US0
21.	Diffraction Element in Extreme-UV Lithography Condenser	07/13/2000	09/615,795	9/4/2001	6,285,497	023890-042	SAND-01042US0
22.	Apparatus and Method for In-Situ Cleaning of Resist Outgassing Windows	1/27/1999	09/238,210	2/27/2001	6,192,897	023890-074	SAND-01074US0
23.	Low Thermal Distortion Extreme-UV Lithography Reticle	7/10/2001	09/903,196	8/27/2002	6,441,885	023890-080	SAND-01080US0
24.	Low Thermal Distortion Extreme-UV Lithography Reticle and Method	7/10/2001	09/903,195	5/28/2002	6,395,455	023890-081	SAND-01081US0



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## LIST OF PENDING PATENT APPLICATIONS

	Title	Filing Date	U.S. Serial No.	Old (BDSM) Attorney Docket No.	New (FDM) Attorney Docket No.
25.	Lithographic focus and Tip/Tilt Sensing for Wafer and/or Reticle Using Absolute-Distance Interferometry	8/16/1999	09/375,847	023890-021	SAND-01021US0
26.	Mask-to-Wafer Alignment System	11/7/2001	09/986,006	023890-023	SAND-01023US0
28.	In-Vacuum Exposure Shutter	7/5/2000	09/610,239	023890-031	SAND-01031US0
28.	Radiation Source With Shaped Emission	12/7/2001	10/005,600	023890-039	SAND-01039US0
29.	EUV Mirror Based Absolute Incident Flux Detector	9/18/2001	09/956,397	023890-041	SAND-01041US0
30.	Cadmium Zinc Telluride X-and Gamma-Ray Detectors	11/17/2000	09/715,391	023890-043	SAND-01043US0
31.	Electrode Configuration for Extreme-UV Electrical Discharge Source	03/13/2001	09/808,587	023890-047	SAND-01047US0
32.	Portable Outgas Detection Apparatus	3/21/2001	09/816,307	023890-048	SAND-01048US0
33.	Method and Apparatus for Reducing Sample Dispersion in Turns and Junctions of Microchannel Systems	11/6/2000	09/707,337	023890-051	SAND-01051US0
34.	Apparatus for In-Situ Cleaning of Carbon Contaminated Surfaces	09/18/2001	09/956,543	023890-052	SAND-01052US0
35.	Capillary Discharge Source	9/18/2001	09/955,658	023890-062	SAND-01062US0

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## LIST OF PENDING PATENT APPLICATIONS

	Title	Filing Date	U.S. Serial No.	Old (BDSM) Attorney Docket No.	New (FDM) Attorney Docket No.
36.	Electrode Configuration for Extreme-UV Electrical Discharge Source	11/21/2002	Unassigned	023890-063	SAND-01063US0
37.	Discharge Source with Gas Curtain for Protection Optics from Particles	9/18/2001	09/956,275	023890-064	SAND-01064US0
38.	Reticle Stage Based Linear Dosimeter	10/2/2002	10/264,062	023890-075	SAND-01075US0
39.	Photoimageable Composition	11/30/2001	09/997,090	023890-078	SAND-01078US0
40.	Method and Apparatus for Detecting the Presence and Thickness of Carbon and Oxide Layers on EUV Reflective Surfaces	6/5/2002	10/163,477	023890-079	SAND-01079US0
41.	Photoimageable Composition	4/17/2002	10/125,134	023890-082	SAND-01082US0
42.	Motorized Support Jack	10/11/2001	09/976,919	023890-084	SAND-01084US0
43.	Condenser for Photolithography System	6/5/2002	10/163,791	023890-086	SAND-01086US0
44.	Extreme-UV Lithography Vacuum Chamber Zone Seal	11/6/2001	09/985,876	023890-088	SAND-01088US0
45.	Extreme-UV Lithography Vacuum Chamber Zone Seal	11/6/2001	09/985,875	023890-089	SAND-01089US0
46.	Adhesive Particle Shielding	9/17/2002	10/245,218	023890-0108	SAND-01108US0

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